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## ABSTRACT

We present a laser-assisted preparation of transparent europium-titanate Eu2Ti2O7 thin films with tailored structural and optical properties. We have evaluated the effects of the irradiation time on the structural and the optical properties of the films. This approach allows the preparation of nanocrystalline crack-free films and micro patterns. The amorphous thin films were prepared by a sol-gel method. The films were annealed by a CO2 laser beam for various time intervals. The laser irradiation induced a crystallization process that resulted in the formation of Eu<sub>2</sub>Ti<sub>2</sub>O<sub>7</sub> nanocrystals. The nanocrystals regularly grew with increasing irradiation time reaching the size from 25 nm to 45 nm. A film of a thickness 480 nm exhibited an optical transmission of 91.9% that is close to the maximal theoretical limit. The film's refractive index at 632 nm was 2.26. A micrometric pattern was prepared by a direct laser writing followed by a wet chemical etching. Feasibility of the demonstrated approach, together with the high film's quality, and europium-titanate chemical resistivity open up many opportunities for advanced applications. The approach can be used for a preparation of protective coatings and integrated photonic devices such as planar optical waveguides and couplers.

#### 1. Introduction

Lanthanide titanium oxides, which crystallize in the face-centered cubic pyrochlore structure with the general formula RE<sub>2</sub>Ti<sub>2</sub>O<sub>7</sub> (RE = rare earth element) [1], have attracted large attention of recent materials research. This family of materials has attracted huge attention for their high thermal stability, chemical resistivity, and low expansion coefficient as perspective materials for thermal barrier coatings [2]. Moreover, the local spin arrangement in the pyrochlore lattice brings phenomenal magnetic properties that strongly depend on the RE incorporated within the pyrochlore crystal lattice [3-5]. For this reason the RE2Ti2O7 compounds have been established as key materials for spintronics [5-7]. However, the effective exploitation of these materials still has been limited because of their crystallization temperatures that are higher than 700 °C [8,9]. High crystallization temperatures prevent the possible preparation of nanocrystalline coatings on commonly used glass substrates and the effective exploitation in integrated devices. A CO<sub>2</sub> laser-assisted treatment can solve this challenge.

CO<sub>2</sub> laser treatment is a powerful method that allows a local surface heating of the materials and minimize the thermal damage to the substrate [10-12]. It has been used for micromachining of glass and ceramics materials [13], to induce a phase transformation of polycrystalline solids [13], etc. Moreover, a laser treatment has been used for the preparation of sophisticated photonics components such as integrated optical waveguides [14], long period gratings [15], etc. All introduced properties make the CO<sub>2</sub> laser treatment suitable for processing of nanocrystalline RE2Ti2O7 thin films.

In this contribution, we present a CO<sub>2</sub> laser-assisted preparation of highly transparent nanocrystalline europium-titanate Eu2Ti2O7 thin films. We study the effects of the annealing time on the formation and the growth of the nanocrystals. We evaluated the film's structural and optical properties. A micro pattern was prepared by a direct laser writing. The results provide fundamental information about the effect of the CO<sub>2</sub> laser treatment on the structural and optical properties of nanocrystalline Eu<sub>2</sub>Ti<sub>2</sub>O<sub>7</sub> thin films. The demonstrated approach allows to preparation of highly transparent films and micrometric patterns that are suitable for a preparation of protective coatings and advanced spintronic devices.

# 2. Materials and methods

### 2.1. Preparation of thin films

The starting sol, that was used to thin film deposition, was prepared

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by an already published approach [16]. Five layers were subsequently dip-coated onto a silica glass substrate (Technical glass products, USA) by a withdrawing speed  $150 \text{ mm min}^{-1}$ . Each layer was densified in a rapid thermal annealing furnace AccuThermo AW410 (Allwin21 corporation) at  $550 \,^{\circ}$ C for 60 s under an oxygen flow of  $5 \, \text{lmin}^{-1}$  and a heating rate of  $10 \,^{\circ}$ C s<sup>-1</sup>.

The densified films were irradiated by a continuous  $CO_2$  laser (SYNRAD 48–1 S) emitting at 10.6  $\mu$ m. A laser beam was expanded to a 5 mm circular spot, a power density of the laser beam was around 20 mW mm<sup>2</sup> and the densified films were irradiated for different time. Alternatively, the laser beam was focused to a 0.5 mm circular spot and the densified films were moved in the beam by means of a computer-controlled X–Y linear translation stage to write a pattern. The stage velocity was 4 mm s<sup>-1</sup>. The irradiated films were alternatively exposed to a 10% water solution of hydrofluoric acid for 300 s to remove the amorphous fraction.

#### 2.2. Characterization techniques

X-ray diffraction (XRD) analyses were obtained on a Bruker D8 Discover diffractometer with a Bragg-Brentano geometry operating with Cu-K $\alpha$  radiation ( $\lambda = 1.54056$  Å, operating voltage 40 kV, current 40 mA, integration time 200 ms). The crystallized phase was compared to JCPDS data file number 23–1072 of Eu<sub>2</sub>Ti<sub>2</sub>O<sub>7</sub>. The mean nanocrystal size was calculated using in-build operating software.

The steady-state luminescence spectra were recorded on a Fluorolog 3 (Horiba Jobin-Yvon) spectrometer equipped with a photomultiplier. The emission spectra were recorded from 570 to 720 nm with a step of 0.5 nm and a slit of 1 nm under the excitation at 394 nm with an excitation slit of 5 nm. The integration time was 0.5 s.

UV–VIS transmission spectra were recorded on a spectrometer Lambda EZ 210 (Perkin-Elmer). The refractive indices were calculated from the transmission spectra by Swanepoel's method for weak absorbing films. According to this method the refractive index n was calculated from the relationship [17]:

$$n = \left\{ \left[ n_{sub} \cdot \frac{T_M - T_m}{T_M \cdot T_m} - \frac{n_{sub}^2 + 1}{2} \right] + \left[ n_{sub} \cdot \frac{T_M - T_m}{T_M \cdot T_m} - \frac{n_{sub}^2 + 1}{2} \right]^{\frac{1}{2}} \right\}^{\frac{1}{2}},$$
(1)

where  $T_M$  represents the transmittance maxima and  $T_m$  represents the transmittance minima of the interference pattern,  $n_{sub}$  is the refractive index of the substrate which is equal to 1.457 for fused silica glass [17].

Scanning electron microscope (SEM) images were taken with a TESCAN Lyra 3 XMU FEG/SEM device (operating voltage 15 kV). A thin carbon layer was sputtered on the samples prior to analyses to prevent sample charging. The thickness and the surface profiles of the samples were measured on an optical profilometer NewView 7300 (Zygo).

### 3. Results and discussion

#### 3.1. Structural characterizations of the films

The effect of the laser annealing on the nanocrystal growth is shown in Fig. 1. The densified film was fully amorphous as can be concluded from the absence of an X-ray diffraction pattern. Broad peaks located between 15° and 40° corresponded to the background signal of the silica substrate. The laser annealing of the amorphous films induced the crystallization of  $Eu_2Ti_2O_7$  and caused a regular growth of the nanocrystals. Formed nanocrystals provided the diffraction pattern typical for  $Eu_2Ti_2O_7$  pyrochlore structure. The diffraction peaks became more intensive and better pronounced with prolonged irradiation time. The absence of the alternative phases; such as  $Eu_2O_3$  or  $TiO_2$ ; confirmed the high purity of the nanocrystals.

Fig. 2 shows the effect of the laser annealing on the luminescence

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Fig. 1. XRD patterns of irradiated samples with denoted (hkl) indices.



Fig. 2. Emission spectra of the laser-annealed films normalized to the intensity of the MD peak at 592 nm.

properties of the films. The particular electronic transitions of Eu<sup>3+</sup> ions were identified according to the literature [6,18]. Densified film exhibited broad peak at 578 nm, which corresponds to  ${}^{5}D_{0} \rightarrow {}^{7}F_{0}$  symmetry forbidden transition. The intensity of the emission peak at 614 nm, which corresponds to the electric-dipole allowed  ${}^{5}D_{0} \rightarrow {}^{7}F_{2}$  (ED) transition, was several times higher than the intensity of the emission peak at 592 nm, which corresponds to the magnetic-dipole allowed  ${}^{5}D_{0} \rightarrow {}^{7}F_{1}$  (MD) transition. The intensities of the peaks located

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